



# 제 31회 한국반도체학술대회

The 31st Korean Conference on Semiconductors

2024년 1월 24일(수)-26일(금) | 경주화백컨벤션센터(HICO)

2024년 1월 26일(금), 09:00-10:45

Room A(101), 1층

## B. Patterning (Lithography & Etch Technology) 분과

### [FA1-B] Lithography and photoresist I

좌장: 성명모 교수(한양대학교), 이진균 교수(인하대학교)

<p>초청발표</p> <p>FA1-B-1</p> <p>09:00-09:30</p>	<p>Spin on Hardmask(SOC)의 소재 개발 동향 및 특성</p> <p>Jin Gon Kim</p> <p>SKMP</p>
<p>FA1-B-2</p> <p>09:30-09:45</p>	<p>Advanced Exposure Technology in ArF Immersion Photolithography</p> <p>Jungchul Song<sup>1,2</sup>, Gyu-Won Han<sup>1</sup>, Jeonghwan Kim<sup>3</sup>, and Ga-Won Lee<sup>2</sup></p> <p><sup>1</sup>NNFC, <sup>2</sup>Division of Electronics Engineering, Chungnam National University, <sup>3</sup>SK Materials Performance</p>
<p>FA1-B-3</p> <p>09:45-10:00</p>	<p>Multi Patterning Technique for Small Pitch of Logic Interconnection</p> <p>Chanho Park, Minkwon Choi, Hyejun Jin, Jeong Hoon Ahn, and Jong-Ho Lee</p> <p>Foundry Business, Samsung Electronics Co., Ltd.</p>
<p>초청발표</p> <p>FA1-B-4</p> <p>10:00-10:30</p>	<p>At Wavelength EUV Metrology and Inspection Technologies</p> <p>Sangsul Lee<sup>1, 2</sup>, Jiho Kim<sup>1</sup>, and Geonhwa Kim<sup>1</sup></p> <p><sup>1</sup>Pohang Accelerator Laboratory, POSTECH, <sup>2</sup>Department of Semiconductor Engineering, POSTECH</p>
<p>FA1-B-5</p> <p>10:30-10:45</p>	<p>Shrinking Contact Hole Patterns by Resist Flow Process and Block Copolymer Technique: Simulation Study</p> <p>Sang-Kon Kim</p> <p>The Faculty of Liberal Arts, Hongik University</p>